Inventor Name Search Result

Your Search was:

Last Name = DOPPER
First Name = GEBHARD

Application#	Patent#	Status	Date Filed	Title	Inventor Name 4
10085527	Not Issued	071	02/28/2002	METHOD AND DEVICE FOR TREATING THE SURFACE OF A PART	DOPPER, GEBHARD
10045770	6602542	150	01/10/2002	DEVICE FOR CLEANING AN ARTICLE	DOPPER, GEBHARD
09840556	6382920	150	04/23/2001	ARTICLE WITH THERMAL BARRIER COATING AND METHOD OF PRODUCING A THERMAL BARRIER COATING	DOPPER, GEBHARD
09840552	Not Issued	071	04/23/2001	PROCESS FOR CLEANING AN ARTICLE, PROCESS FOR COATING AN ARTICLE, AND DEVICE THEREFOR	DOPPER, GEBHARD

Inventor Search Completed: No Records to Display.

Search Another: Inventor

Last Name	First Name	
DOPPER	GEBHARD	Search

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L Number	Hits	Search Text	DB	Time stamp
1	1	6602542.pn.or6382920.pn.	USPAT; US-PGPUB	2003/11/21 08:55
2	2	6602542.pn. or 6382920.pn.	USPAT; US-PGPUB	2003/11/21 08:57
3	0	427/532,533,534,535	USPAT; US-PGPUB	2003/11/21 08:58
4	1077	(427/532,533,534,535).CCLS.	USPAT; US-PGPUB	2003/11/21 08:58
5	280	(427/551).CCLS.	USPAT; US-PGPUB	2003/11/21 08:58
6	746	(427/596,597).CCLS.	USPAT; US-PGPUB	2003/11/21 08:58
7	919	(427/255.11,255.19,255.21,255.5).CCLS.	USPAT; US-PGPUB	2003/11/21 08:58
8	734	(427/318,319).CCLS.	USPAT; US-PGPUB	2003/11/21 08:58
9	2014	(216/63,64,67,74,75).CCLS.	USPAT; US-PGPUB	2003/11/21 08:59
10	1291	(204/192.32,192.35,298.31,298.34).CCLS.	USPAT; US-PGPUB	2003/11/21 08:59
11	6535	((427/532,533,534,535).CCLS.) ((427/551).CCLS.) ((427/596,597).CCLS.) ((427/255.11,255.19,255.21,255.5).CCLS.) ((427/318,319).CCLS.) ((216/63,64,67,74,75).CCLS.) ((204/192.32,192.35,298.31,298.34).CCLS.)	USPAT; US-PGPUB	2003/11/21 08:59
12	3	(clean$3 near5 (plasma or (glow adj discharge) or sputter$3 or ion)) and (electron with (flow$3 or flux$3) with (control$5 or switch$3)) and (Dopper.in. or Siemens.as.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/21 09:02
13	9	(clean$3 near5 (plasma or (glow adj discharge) or sputter$3 or ion)) and (electron with (flow$3 or flux$3) with (control$5 or switch$3)) and (((427/532,533,534,535).CCLS.) ((427/551).CCLS.) ((427/596,597).CCLS.) ((427/255.11,255.19,255.21,255.5).CCLS.) ((427/318,319).CCLS.) ((216/63,64,67,74,75).CCLS.) ((204/192.32,192.35,298.31,298.34).CCLS.))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/21 09:11
14	7	((clean$3 near5 (plasma or (glow adj discharge) or sputter$3 or ion)) and (electron with (flow$3 or flux$3) with (control$5 or switch$3)) and (((427/532,533,534,535).CCLS.) ((427/551).CCLS.) ((427/596,597).CCLS.) ((427/255.11,255.19,255.21,255.5).CCLS.) ((427/318,319).CCLS.) ((216/63,64,67,74,75).CCLS.) ((204/192.32,192.35,298.31,298.34).CCLS.))) not ((clean$3 near5 (plasma or (glow adj discharge) or sputter$3 or ion)) and (electron with (flow$3 or flux$3) with (control$5 or switch$3)) and (Dopper.in. or Siemens.as.))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/21 09:02
15	2	(((427/532,533,534,535).CCLS.) ((427/551).CCLS.) ((427/596,597).CCLS.) ((427/255.11,255.19,255.21,255.5).CCLS.) ((427/318,319).CCLS.) ((216/63,64,67,74,75).CCLS.) ((204/192.32,192.35,298.31,298.34).CCLS.)) and ((electron near3 heat$3) same ((plasma or ion or sputter$3 or (glow adj discharge)) near3 clean$3))	USPAT; US-PGPUB	2003/11/21 09:05
16	49	((electron near5 heat$3) same ((plasma or ion or sputter$3 or (glow adj discharge)) near5 clean$3))	USPAT; US-PGPUB	2003/11/21 09:09

17	47	(((electron near5 heat$3) same ((plasma or ion or sputter$3 or (glow adj discharge)) near5 clean$3))) not ((((427/532,533,534,535).CCLS.) ((427/551).CCLS.) ((427/596,597).CCLS.) ((427/255.11,255.19,255.21,255.5).CCLS.) ((427/318,319).CCLS.) ((216/63,64,67,74,75).CCLS.) ((204/192.32,192.35,298.31,298.34).CCLS.)) and ((electron near3 heat$3) same ((plasma or ion or sputter$3 or (glow adj discharge)) near3 clean$3)))	USPAT; US-PGPUB	2003/11/21 09:05
18	21	((electron near5 heat$3) same ((plasma or ion or sputter$3 or (glow adj discharge)) near5 clean$3))	EPO; JPO; DERWENT; IBM_TDB	2003/11/21 09:09
19	100	(clean$3 near5 (plasma or (glow adj discharge) or sputter$3 or ion)) and (electron with (flow$3 or flux$3) with (control$5 or switch$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/21 09:26
20	91	((clean$3 near5 (plasma or (glow adj discharge) or sputter$3 or ion)) and (electron with (flow$3 or flux$3) with (control$5 or switch$3))) not ((clean$3 near5 (plasma or (glow adj discharge) or sputter$3 or ion)) and (electron with (flow$3 or flux$3) with (control$5 or switch$3)) and (((427/532,533,534,535).CCLS.) ((427/551).CCLS.) ((427/596,597).CCLS.) ((427/255.11,255.19,255.21,255.5).CCLS.) ((427/318,319).CCLS.) ((216/63,64,67,74,75).CCLS.) ((204/192.32,192.35,298.31,298.34).CCLS.)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/21 09:15
21	137	(((427/532,533,534,535).CCLS.) ((427/551).CCLS.) ((427/596,597).CCLS.) ((427/255.11,255.19,255.21,255.5).CCLS.) ((427/318,319).CCLS.)) and (((216/63,64,67,74,75).CCLS.) ((204/192.32,192.35,298.31,298.34).CCLS.))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/21 09:16
22	6	(((427/532,533,534,535).CCLS.) ((427/551).CCLS.) ((427/596,597).CCLS.) ((427/255.11,255.19,255.21,255.5).CCLS.) ((427/318,319).CCLS.) ((216/63,64,67,74,75).CCLS.) ((204/192.32,192.35,298.31,298.34).CCLS.)) and ((alternat$4 or switch$3) with ((electron near2 (heat$3 or bombard$5)) or (positiv$3 near2 bias)) with (((sputter$3 or plasma or (glow adj discharge) or ion) near2 (clean$3 or bombard$5)) or (negativ$4 near2 bias)))	USPAT; US-PGPUB	2003/11/21 09:20
23	259	((alternat$4 or switch$3) with ((electron near2 (heat$3 or bombard$5)) or (positiv$3 near2 bias)) with (((sputter$3 or plasma or (glow adj discharge) or ion) near2 (clean$3 or bombard$5)) or (negativ$4 near2 bias)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/21 09:21
24	59	(((alternat$4 or switch$3) with ((electron near2 (heat$3 or bombard$5)) or (positiv$3 near2 bias)) with (((sputter$3 or plasma or (glow adj discharge) or ion) near2 (clean$3 or bombard$5)) or (negativ$4 near2 bias)))) and ((coat$3 or $4CVD or deposit$3) near5 (substrate or base or metal$4 or turbine or structure or body or basebody))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/21 09:28
25	207	(electron with (flow$3 or flux$3 or outflow$3 or outflux$3) with (control$5) with (switch$3 or alternat$5 or (open$3 near3 clos$3)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/21 09:27

26	223	(electron with (flow$3 or flux$3 or outflow$3 or outflux$3) with (control$5 or regulat$3 or adjust$3) with (switch$3 or alternat$5 or (open$3 near3 clos$3)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/21 09:28
27	3	((electron with (flow$3 or flux$3 or outflow$3 or outflux$3) with (control$5 or regulat$3 or adjust$3) with (switch$3 or alternat$5 or (open$3 near3 clos$3)))) and (((427/532,533,534,535).CCLS.) ((427/551).CCLS.) ((427/596,597).CCLS.) ((427/255.11,255.19,255.21,255.5).CCLS.) ((427/318,319).CCLS.) ((216/63,64,67,74,75).CCLS.) ((204/192.32,192.35,298.31,298.34).CCLS.))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/21 09:28
28	71	((electron with (flow$3 or flux$3 or outflow$3 or outflux$3) with (control$5 or regulat$3 or adjust$3) with (switch$3 or alternat$5 or (open$3 near3 clos$3)))) and ((coat$3 or $4CVD or deposit$3) near5 (substrate or base or metal$4 or turbine or structure or body or basebody))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/21 09:28
29	65	(((electron with (flow$3 or flux$3 or outflow$3 or outflux$3) with (control$5 or regulat$3 or adjust$3) with (switch$3 or alternat$5 or (open$3 near3 clos$3)))) and ((coat$3 or $4CVD or deposit$3) near5 (substrate or base or metal$4 or turbine or structure or body or basebody))) not (((((electron with (flow$3 or flux$3 or outflow$3 or outflux$3) with (control$5 or regulat$3 or adjust$3) with (switch$3 or alternat$5 or (open$3 near3 clos$3)))) and (((427/532,533,534,535).CCLS.) ((427/551).CCLS.) ((427/596,597).CCLS.) ((427/255.11,255.19,255.21,255.5).CCLS.) ((427/318,319).CCLS.) ((216/63,64,67,74,75).CCLS.) ((204/192.32,192.35,298.31,298.34).CCLS.))) or ((((alternat$4 or switch$3) with ((electron near2 (heat$3 or bombard$5)) or (positiv$3 near2 bias)) with (((sputter$3 or plasma or (glow adj discharge) or ion) near2 (clean$3 or bombard$5)) or (negativ$4 near2 bias)))) and ((coat$3 or $4CVD or deposit$3) near5 (substrate or base or metal$4 or turbine or structure or body or basebody))))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/21 09:29